	Hits	Search Text	DBs	Time Stamp
1	0	maskless adj lithographic adj pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 10:57
2	975	((mask?less) (without near2 mask)) near3 pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:36
3	1	((mask?less) (without near2 mask)) near3 pattern and exposure adj (cell cells)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:55
4	151	((mask?less) (without near2 mask)) near3 pattern and (cell cells)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 15:44
5	135	((mask?less) (without near2 mask)) near3 pattern and (cell cells) and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:16
6	7	((mask?less) (without near2 mask)) near3 pattern same (cell cells) and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:13
7	24	((mask?less) (without near2 mask)) near3 pattern and (cell cells) and substrate and lithographic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:16
8	540	((mask?less) (without near2 mask)) near3 pattern and (electron electrons cell cells)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:20
9	498	((mask?less) (without near2 mask)) near3 pattern and (electron electrons cell cells) and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:23

	Hits	Search Text	DBs	Time Stamp
10	21	((mask?less) (without near2 mask)) near3 pattern and (cell cells) and substrate and stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:45
11	53	((mask?less) (without near2 mask)) near3 pattern same (electron electrons cell cells) and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:23
12	3	((mask?less) (without near2 mask)) near3 pattern same (electron electrons cell cells) and substrate and stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:23
13	23	("4604162" "4849857" "4928058" "4990462" "5110712" "5119164" "5284804" "5480842" "5470693" "5733814" "37637").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:37
14	0	((mask?less) (without near2 mask)) near3 pattern and S13	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:49
15	10	pattern and S13	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:44
16	7	pattern and S13 and (mask masks)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:44
17	2	"4934799".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:41
18	0	((mask?less) (without near2 mask)) near3 pattern and S17	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:42

	Hits	Search Text	DBs	Time Stamp
19	2	pattern and S17	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:49
20	1	pattern and S17 and (mask masks)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:43
21	0	((mask?less) (without near2 mask)) near3 pattern and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:44
22	2	pattern and S21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:44
23	1	pattern and S21 and (mask masks)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:49
24	10	("4724328" "4994336" "5358909" "5514628" "5620915").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:46
25	7	("6230233" "6445006" "6682981" "6713327").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:48
26	7	("4835765" "4919749" "5144142" "5262341").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:48
27	0	((mask?less) (without near2 mask)) near3 pattern and S26	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:57

	Hits	Search Text	DBs	Time Stamp
28	5	pattern and S26	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:57
29	4	pattern and S26 and (mask masks)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:58
30	4	("4897708" "4983251").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:52
31	24	("4500905" "4939568" "4892753" "500113" "5240458" "5259247" "34893" "6087284" "651803").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:53
32	69	("2915722" "3202948" "3559282" "3560364" "3602982" "3615901" "3716429" "3777227" "3868565" "3922705" "3997381" "4070230" "4131985" "4142004" "4251909" "4262631" "4394401" "4401986" "4416054" "4539068" "4585991" "4612083" "4617160" "4618397" "4618763" "4663559" "4684436" "4693770").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 11:57
33	0	((mask?less) (without near2 mask)) near3 pattern and S32	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:01
34	15	pattern and S32	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:01
35	5	pattern and S32 and (mask masks)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:01

	Hits	Search Text	DBs	Time Stamp
36	58	("4702336" "4702936" "4706166" "4721938" "4761681" "4784721" "4810673" "4825277" "4857481" "4924589" "4940916" "4950987" "4952446" "4954865" "4957882" "4965415" "4966663" "4994735" "5008619" "5010024" "5020219" "5034685" "5070026" "5071510" "5098865" "5103557" "5110373" "5111278" "5116777" "5130894" "5132244").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:01
37	0	((mask?less) (without near2 mask)) near3 pattern and S36	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:08
38	21	pattern and S36	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:08
39	15	pattern and S36 and (mask masks)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:08
40	62	("5151775" "5156909" "5203731" "5225771" "5236118" "5262351" "5270261" "5273940" "5274270" "5279865" "5284796" "5323035" "5324687" "5354695" "5363021" "5385909" "5385632" "5420458" "5242920" "5426072" "5426363" "5432444" "5432729" "5434500" "5451489" "5453404" "5457879" "5476813" "5489554" "5502667" "5512397" "5527645").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:05

	Hits	Search Text	DBs	Time Stamp
41	55	("5529829" "5534465" "5555212" "5563084" "5571741" "5580687" "5581498" "5582939" "5583688" "5592007" "5592018" "5595933" "5606186" "5627112" "5629137" "5633209" "5637536" "5654127" "5654220" "5656552" "5675185" "5964588" "5725995" "5750211" "5760478" "5773152" "5786116" "5793115" "5831280" "5834334" "5840593" "5856695").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:08
42	0	((mask?less) (without near2 mask)) near3 pattern and S40	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:08
43	0	((mask?less) (without near2 mask)) near3 pattern and S41	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:14
44	22	pattern and S40	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:08
45	29	pattern and S41	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:08
46	17	pattern and S40 and (mask masks)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:14
47	23	pattern and S41 and (mask masks)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:12

	Hits	Search Text	DBs	Time Stamp
48	38	("5868949" "5869354" "5870176" "5880010" "5882532" "5902118" "5915167" "5946559" "5985693" "5998069" "6008126" "6020257" "6045625" "6084284" "6097096" "6133640" "6194245" "6197456" "6208545" "6236602" "6261728" "6288561" "6294909").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:14
49	0	((mask?less) (without near2 mask)) near3 pattern and S48	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:14
50	21	pattern and S48	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:14
51	19	pattern and S48 and (mask masks)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:14
52	1	((mask?less) (without near2 mask)) near3 pattern and ((radiation adj source) (shuttered adj cell)) and electro?magnetic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:37
53	12	((mask?less) (without near2 mask)) near3 pattern and electro?magnetic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:38
54	42	((mask?less) (without near2 mask)) near3 pattern and ((radiation adj source) (shuttered adj cell))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:39
55	63	((mask?less) (without near2 mask)) near3 pattern and (electron electrons cell cells) and substrate and stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:46

	Hits	Search Text	DBs	Time Stamp
56	3	((mask?less) (without near2 mask)) near3 pattern same (electron electrons cell cells) and substrate and stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 15:49
57	30	((mask?less) (without near2 mask)) near3 pattern and (electron electrons cell cells) and substrate same stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:49
58	10	("4515876" | "4592081" | "5101420" | "5166962" | "5188706" | "5196283" | "5291536" | "5496667" | "5541023" | "5553110").PN.	US-PGPUB; USPAT; USOCR	2005/11/21 12:48
59	0	((mask?less) (without near2 mask)) near3 pattern and S58 and stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:49
60	0	((mask?less) (without near2 mask)) near3 pattern and S58	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:49
61	8	S58 and stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:14
62	38	((mask?less) (without near2 mask)) near3 pattern and exposure near2 x?ray	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:14
63	2	"4704020".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/21 12:58
64	4	("5354695" "5869354" "6714625").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 14:58

	Hits	Search Text	DBs	Time Stamp
65	582	((mask?less) (without near2 mask)) near3 pattern and (electrons electron particle particles cell cells)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 15:46
66	531	((mask?less) (without near2 mask)) near3 pattern and (electrons electron particle particles cell cells) and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:01
67	0	((mask?less) (without near2 mask)) near3 pattern and (electrons electron particle particles cell cells) with electro?magnetic and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 15:47
68	0	((mask?less) (without near2 mask)) near3 pattern and (electrons electron particle particles cell cells) same electro?magnetic and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 15:47
69	9	((mask?less) (without near2 mask)) near3 pattern and (electrons electron particle particles cell cells) and electro?magnetic and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 15:47
70	71	((mask?less) (without near2 mask)) near3 pattern and (electrons electron particle particles cell cells) with (radiation shutter) and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 15:56
71	71	((mask?less) (without near2 mask)) near3 pattern same (electrons electron particle particles cell cells) and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 15:50
72	44	((mask?less) (without near2 mask)) near3 pattern with (electrons electron particle particles cell cells) and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:00
73	65	((mask?less) (without near2 mask)) near3 pattern and (particle particles electron electrons cell cells) and substrate and stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 15:50

	Hits	Search Text	DBs	Time Stamp
74	4	("4023904" | "4815854" | "4947413" | "5424549").PN.	US-PGPUB; USPAT; USOCR	2005/11/26 15:52
75	23	("5900637").URPN.	USPAT	2005/11/26 15:55
76	16	((mask?less) (without near2 mask)) near3 pattern and (electrons electron particle particles cell cells) with (radiation shutter) and substrate and shutter	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 15:56
77	5	((mask?less) (without near2 mask)) near3 pattern with (electrons electron particle particles cell cells) and substrate and stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:00
78	7	((mask?less) (without near2 mask)) near3 pattern same (electrons electron particle particles cell cells) and substrate and stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:00
79	6	((mask?less) (without near2 mask)) near3 pattern and (electrons electron particle particles cell cells) and substrate and stress with dielectric	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:02
80	18	((mask?less) (without near2 mask)) near3 pattern and (electrons electron particle particles cell cells) and substrate and stress with layer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:08
81	65	((mask?less) (without near2 mask)) near3 pattern and (electrons electron particle particles cell cells) and substrate and stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:10
82	18	((mask?less) (without near2 mask)) near3 pattern and (electrons electron particle particles cell cells) and stress with layer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:08

	Hits	Search Text	DBs	Time Stamp
83	5176	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:10
84	344	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and stress with dielectric	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:10
85	109	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and stress near2 dielectric	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:39
86	42	((mask?less) (without near2 mask) mask) near3 pattern same (electrons electron particle particles cell cells) and substrate and stress with dielectric	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:11
87	8	((mask?less) (without near2 mask) mask) near3 pattern same (electrons electron particle particles cell cells) and substrate and stress near2 dielectric	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:12
88	5	((mask?less) (without near2 mask)) near3 pattern and exposure near2 x?ray and stress	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:14
89	10	("4515876" | "4592081" | "5101420" | "5166962" | "5188706" | "5196283" | "5291536" | "5496667" | "5541023" | "5553110").PN.	US-PGPUB; USPAT; USOCR	2005/11/26 16:14
90	8	S90 and stress and mask	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:15

	Hits	Search Text	DBs	Time Stamp
91	8	S90 and stress and mask and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:15
92	7	S90 and stress and mask and pattern and (electrons electron particle particles cell cells)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:16
93	7	S90 and stress and mask same pattern and (electrons electron particle particles cell cells)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:16
94	48	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and stress near2 dielectric with (silicon adj (dioxide nitride))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:40
95	49	((mask?less) (without near2 mask) mask) near3 pattern and substrate and stress near2 dielectric with (silicon adj (dioxide nitride))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:40
96	722	((mask?less) (without near2 mask) mask) near3 pattern and substrate and stress with (silicon adj (dioxide nitride))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:40
97	517	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and stress with (silicon adj (dioxide nitride))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:53
98	136	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and stress with (silicon adj (dioxide nitride) adj layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:41

	Hits	Search Text	DBs	Time Stamp
99	127	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and stress near8 (silicon adj (dioxide nitride) adj layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:41
100	50	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and stress near3 (silicon adj (dioxide nitride) adj layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:45
101	153	((mask?less) (without near2 mask) mask) near3 pattern and substrate and stress with fracture	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:45
102	37	((mask?less) (without near2 mask) mask) near3 pattern and substrate and stress with fracture adj strength	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:47
103	51	((mask?less) (without near2 mask) mask) near3 pattern and substrate and stress same fracture adj strength	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:53
104	5343	((mask?less) (without near2 mask) mask) near3 pattern and substrate and electromagnetic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:53
105	4204	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and electromagnetic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:54
106	1416	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and electromagnetic with (electrons electron particle particles cell cells)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:54

	Hits	Search Text	DBs	Time Stamp
107	72	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and electromagnetic with (electrons electron particle particles cell cells) with array	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:54
108	61	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and electromagnetic with (electrons electron particle particles cell cells) with array and (lithographic lithography)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:55
109	1041	((mask?less) (without near2 mask) mask) near3 pattern and (electrons electron particle particles cell cells) and substrate and electromagnetic with (electrons electron particle particles cell cells) and (lithographic lithography)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 16:58
110	908	438/795.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:31
111	566	438/690.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:27
112	830	378/34.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:27
113	791	378/35.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:27

	Hits	Search Text	DBs	Time Stamp
114	7688	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:27
115	1	S115 and ((mask?less) (without near2 mask)) near3 pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:28
116	2	S116 and ((mask?less) (without near2 mask)) near3 pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:28
117	16	S117 and ((mask?less) (without near2 mask)) near3 pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:29
118	12	S118 and ((mask?less) (without near2 mask)) near3 pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:30
119	91	S119 and ((mask?less) (without near2 mask)) near3 pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:31
120	205	438/942.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:31
121	170	438/948.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:31
122	378	438/949.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:31

	Hits	Search Text	DBs	Time Stamp
123	0	S126 and ((mask?less) (without near2 mask)) near3 pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:32
124	1	S125 and ((mask?less) (without near2 mask)) near3 pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:32
125	1	S127 and ((mask?less) (without near2 mask)) near3 pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/11/26 17:32